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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :
Jun HATAKEYAMA et al. : Examiner: Rosemary E. Ashton
Serial No.: 09/842,114 : Art Unit: 1752
Filed: April 26, 2001 :
For: POLYMER, CHEMICALLY AMPLIFIED RESIST COMPOSITION AND
PATTERNING PROCESS

REPLY UNDER 37 CFR §1.116

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated July 29, 2004, please amend the application as follows and consider the remarks.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 20 of this paper.